

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	"20050224452"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:13
L2	36	(@ad<="20020417") and (216/41. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:16
L3	33	(@ad<="20020417") and (216/58. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:16
L4	164	(@ad<="20020417") and (438/694. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:16
L5	60	(@ad<="20020417") and (427/256. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:17
L6	31	(@ad<="20020417") and (257/622. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:17
L7	146	(@ad<="20020417") and (430/56. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:17
S1	0	(@ad<="20030409") and (microlithograph\$4) and silane and nanocomposit	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:20

EAST Search History

S2	565	(@ad<="20030409") and (microlithograph\$4) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:21
S3	93	(@ad<="20030409") and (microlithograph\$4) and silane and nanoparticles	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:23
S4	2	(@ad<="20030409") and (microlithograph\$4) and silane and nanoparticles and nanoimprint	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:27
S5	5	(@ad<="20030409") and resist and silane and nanoparticles and nanoimprint	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:30
S6	191	(@ad<="20030409") and resist and silane and nanoparticles	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:31
S7	92	(@ad<="20030409") and resist and silane and nanoparticles and radical	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 09:58
S8	2	("20050101698").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/18 19:19
S9	0	("20010952135").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/18 19:20

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S10	0	("2001952135").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/18 19:20
S11	10171	((@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant or ("UV" with absorb\$4))))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:04
S12	234	((@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:04
S13	39	((@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:08
S14	0	((@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4) and silane and nanoparticle	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/21 09:53
S15	2	((@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4) and silane and (nano\$5 with particle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:06
S16	21	((@ad<="20020417") and ((photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:21
S17	22	((@ad<="20020417") and ((photoresist) with "UV" with absorb\$4) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:29

EAST Search History

S18	5	(@ad<="20020417") and ((photoresist) with "UV" with absorb\$4) and silane and novolak	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:47
S19	649	(@ad<="20020417") and ((photoresist) with nano\$6)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:48
S20	9	(@ad<="20020417") and ((photoresist) with nano\$6 with particles)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 12:45
S21	15	(@ad<="20020417") and lithograph\$3 and (sol or sol\$1gel) and nano and bottom and imprint	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:38
S22	4	(@ad<="20020417") and lithograph\$3 and imprint and (etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:46
S23	0	(@ad<="20020417") and lithograph\$3 and (nanocomposit with etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:47
S24	0	(@ad<="20020417") and lithograph\$3 and (nanoscale with etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:48
S25	0	(@ad<="20020417") and lithograph\$3 and (nano\$6 with etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:48

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S26	0	(@ad<="20020417") and lithograph\$3 and (residual with etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 13:34
S27	3	(@ad<="20020417") and lithograph\$3 and (residu\$3 with etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:49
S28	2	("20050224452").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/21 09:51
S29	0	(@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4) and silane and nanoparticle and (polymer with aromatic with (novolaks or styrenes or "(poly)hydroxystyrenes" or "(meth)acrylates"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/21 09:57
S30	891	(@ad<="20020417") and (resist or photoresist) and (polymer with aromatic with (novolaks or styrenes or "(poly)hydroxystyrenes" or "(meth)acrylates"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/21 09:57
S31	0	(@ad<="20020417") and ((multi-level) with (resist or photoresist)) and (polymer with aromatic with (novolaks or styrenes or "(poly)hydroxystyrenes" or "(meth)acrylates"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/21 09:58
S32	12	(@ad<="20020417") and ((multi) with (resist or photoresist)) and (polymer with aromatic with (novolaks or styrenes or "(poly)hydroxystyrenes" or "(meth)acrylates"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/21 09:59
S33	2407	(@ad<="20020417") and (216/67.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 13:34

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S34	201	(@ad<="20020417") and (216/67. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:15
S35	3	(@ad<="20020417") and (216/67. ccls.) and (silane with polymeriz\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 14:43
S36	1	(@ad<="20020417") and (264/129. ccls.) and (silane with polymeriz\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 14:56
S37	0	(@ad<="20020417") and (264/219. ccls.) and (silane with polymeriz\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 14:56
S38	0	(@ad<="20020417") and (264/239. ccls.) and (silane with polymeriz\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 14:56

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L1	2	"20050224452"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:13
L2	36	(@ad<="20020417") and (216/41. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:16
L3	33	(@ad<="20020417") and (216/58. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:16
L4	164	(@ad<="20020417") and (438/694. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:16
L5	60	(@ad<="20020417") and (427/256. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:17
L6	31	(@ad<="20020417") and (257/622. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:17
L7	146	(@ad<="20020417") and (430/56. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:17
S1	0	(@ad<="20030409") and (microlithograph\$4) and silane and nanocomposit	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:20

EAST Search History

S2	565	(@ad<="20030409") and (microlithograph\$4) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:21
S3	93	(@ad<="20030409") and (microlithograph\$4) and silane and nanoparticles	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:23
S4	2	(@ad<="20030409") and (microlithograph\$4) and silane and nanoparticles and nanoimprint	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:27
S5	5	(@ad<="20030409") and resist and silane and nanoparticles and nanoimprint	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:30
S6	191	(@ad<="20030409") and resist and silane and nanoparticles	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/16 13:31
S7	92	(@ad<="20030409") and resist and silane and nanoparticles and radical	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 09:58
S8	2	("20050101698").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/18 19:19
S9	0	("20010952135").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/18 19:20

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S10	0	("2001952135").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/18 19:20
S11	10171	(@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant or ("UV" with absorb\$4)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:04
S12	234	(@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:04
S13	39	(@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:08
S14	0	(@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4) and silane and nanoparticle	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/21 09:53
S15	2	(@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4) and silane and (nano\$5 with particle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:06
S16	21	(@ad<="20020417") and ((photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:21
S17	22	(@ad<="20020417") and ((photoresist) with "UV" with absorb\$4) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:29

EAST Search History

S18	5	(@ad<="20020417") and ((photoresist) with "UV" with absorb\$4) and silane and novolak	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:47
S19	649	(@ad<="20020417") and ((photoresist) with nano\$6)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 10:48
S20	9	(@ad<="20020417") and ((photoresist) with nano\$6 with particles)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 12:45
S21	15	(@ad<="20020417") and lithograph\$3 and (sol or sol\$1gel) and nano and bottom and imprint	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:38
S22	4	(@ad<="20020417") and lithograph\$3 and imprint and (etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:46
S23	0	(@ad<="20020417") and lithograph\$3 and (nanocomposit with etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:47
S24	0	(@ad<="20020417") and lithograph\$3 and (nanoscale with etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:48
S25	0	(@ad<="20020417") and lithograph\$3 and (nano\$6 with etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:48

EAST Search History

S26	0	(@ad<="20020417") and lithograph\$3 and (residual with etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 13:34
S27	3	(@ad<="20020417") and lithograph\$3 and (residu\$3 with etch\$3 with (oxygen or o2 or "o.sub.2") with (chf3 or "chf.sub.3"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/19 14:49
S28	2	("20050224452").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/21 09:51
S29	0	(@ad<="20020417") and ((resist or photoresist) with (dense or flexibe or resistant)) and ("UV" with absorb\$4) and silane and nanoparticle and (polymer with aromatic with (novolaks or styrenes or "(poly)hydroxystyrenes" or "(meth)acrylates"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/21 09:57
S30	891	(@ad<="20020417") and (resist or photoresist) and (polymer with aromatic with (novolaks or styrenes or "(poly)hydroxystyrenes" or "(meth)acrylates"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/21 09:57
S31	0	(@ad<="20020417") and ((multi-level) with (resist or photoresist)) and (polymer with aromatic with (novolaks or styrenes or "(poly)hydroxystyrenes" or "(meth)acrylates"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/21 09:58
S32	12	(@ad<="20020417") and ((multi) with (resist or photoresist)) and (polymer with aromatic with (novolaks or styrenes or "(poly)hydroxystyrenes" or "(meth)acrylates"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/21 09:59
S33	2407	(@ad<="20020417") and (216/67.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 13:34

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S34	201	(@ad<="20020417") and (216/67. ccls.) and silane	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/20 15:15
S35	3	(@ad<="20020417") and (216/67. ccls.) and (silane with polymeriz\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 14:43
S36	1	(@ad<="20020417") and (264/129. ccls.) and (silane with polymeriz\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 14:56
S37	0	(@ad<="20020417") and (264/219. ccls.) and (silane with polymeriz\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 14:56
S38	0	(@ad<="20020417") and (264/239. ccls.) and (silane with polymeriz\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 14:56